

US 20130136991A1

(19) **United States**

(12) **Patent Application Publication**
Merrill et al.

(10) **Pub. No.: US 2013/0136991 A1**

(43) **Pub. Date: May 30, 2013**

(54) **HIGH ENERGY/POWER DENSITY NICKEL
OXIDE/HYDROXIDE MATERIALS AND
NICKEL COBALT OXIDE/HYDROXIDE
MATERIALS AND PRODUCTION THEREOF**

Publication Classification

(51) **Int. Cl.**
H01M 4/525 (2006.01)
H01M 4/04 (2006.01)
(52) **U.S. Cl.**
CPC *H01M 4/525* (2013.01); *H01M 4/0452*
(2013.01); *Y10S 977/755* (2013.01); *B82Y*
30/00 (2013.01)
USPC **429/223**; 205/60; 252/182.1; 252/513;
977/755

(71) Applicant: **Lawrence Livermore National
Security, LLC**, Livermore, CA (US)

(72) Inventors: **Matthew Merrill**, Dublin, CA (US);
Michael Stadermann, Pleasanton, CA
(US)

(73) Assignee: **LAWRENCE LIVERMORE
NATIONAL SECURITY, LLC**,
Livermore, CA (US)

(21) Appl. No.: **13/685,567**

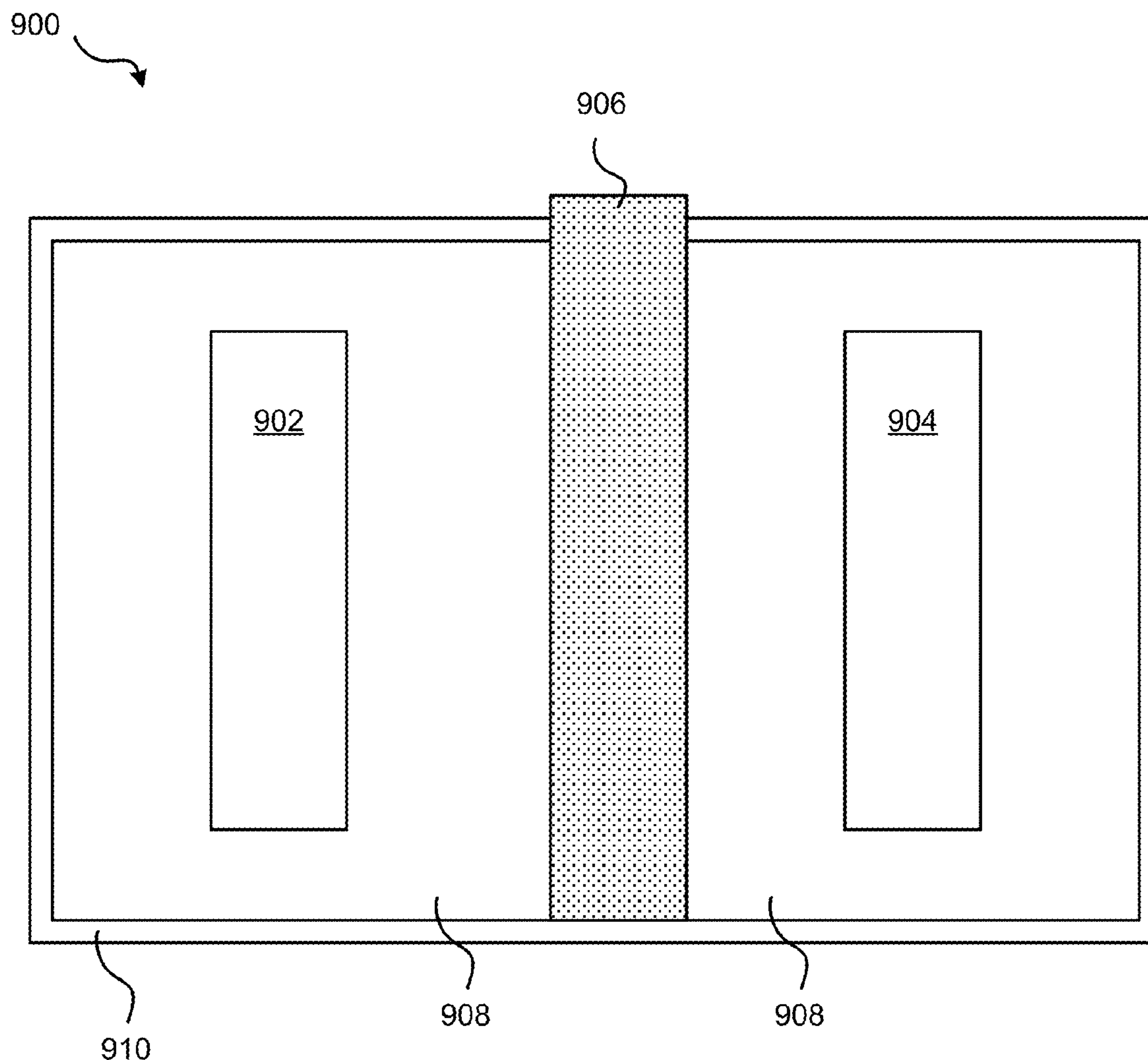
(22) Filed: **Nov. 26, 2012**

Related U.S. Application Data

(60) Provisional application No. 61/565,444, filed on Nov.
30, 2011.

(57) **ABSTRACT**

According to one embodiment, a material includes a nickel
oxide/hydroxide active film, wherein the nickel oxide/hy-
droxide active film has a physical characteristic of maintain-
ing greater than about 80% charge over greater than 500
charge/discharge cycles, and wherein the nickel oxide/hy-
droxide active film has a physical characteristic of storing
electrons at greater than about 0.5 electron per nickel atom.



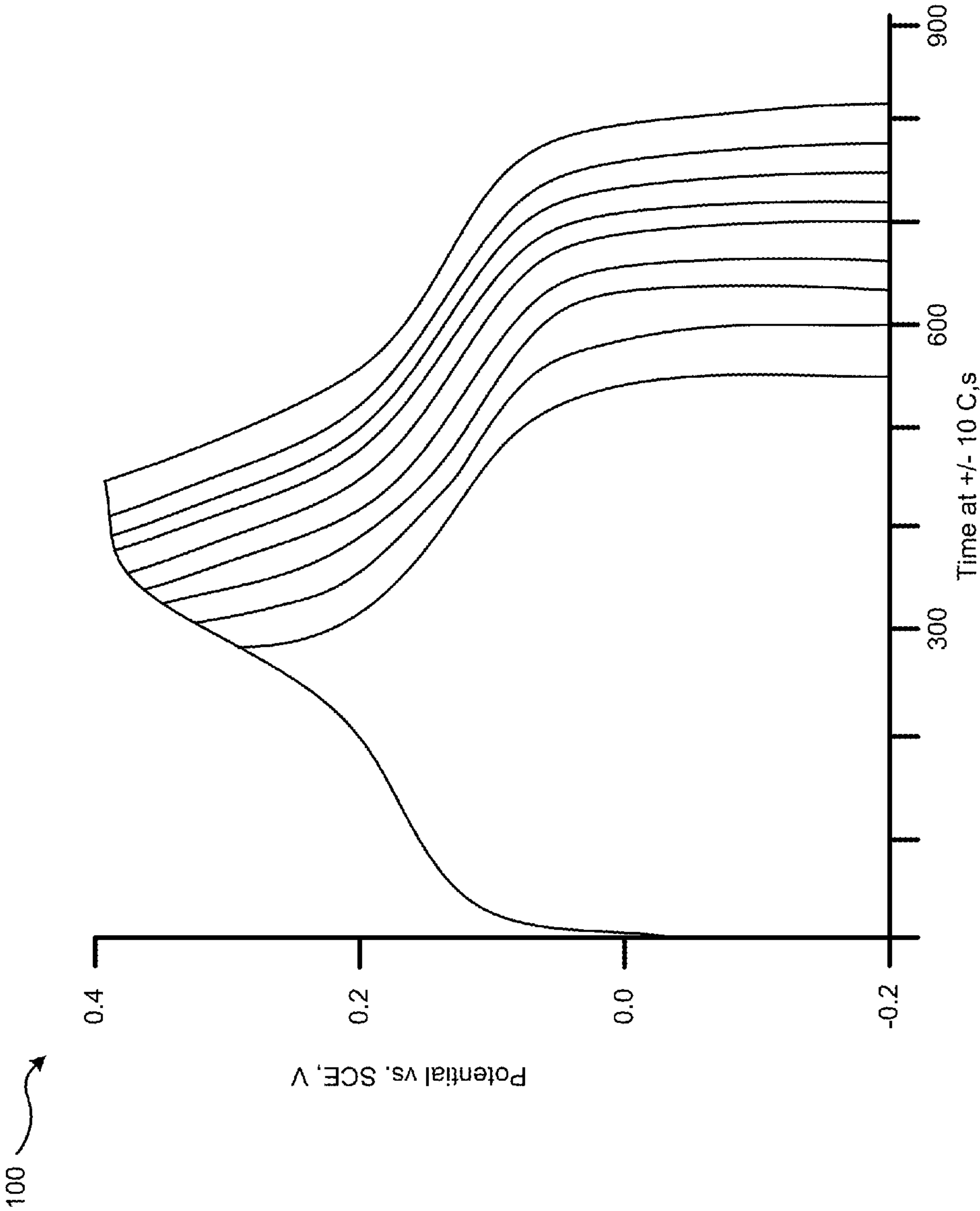


FIG. 1

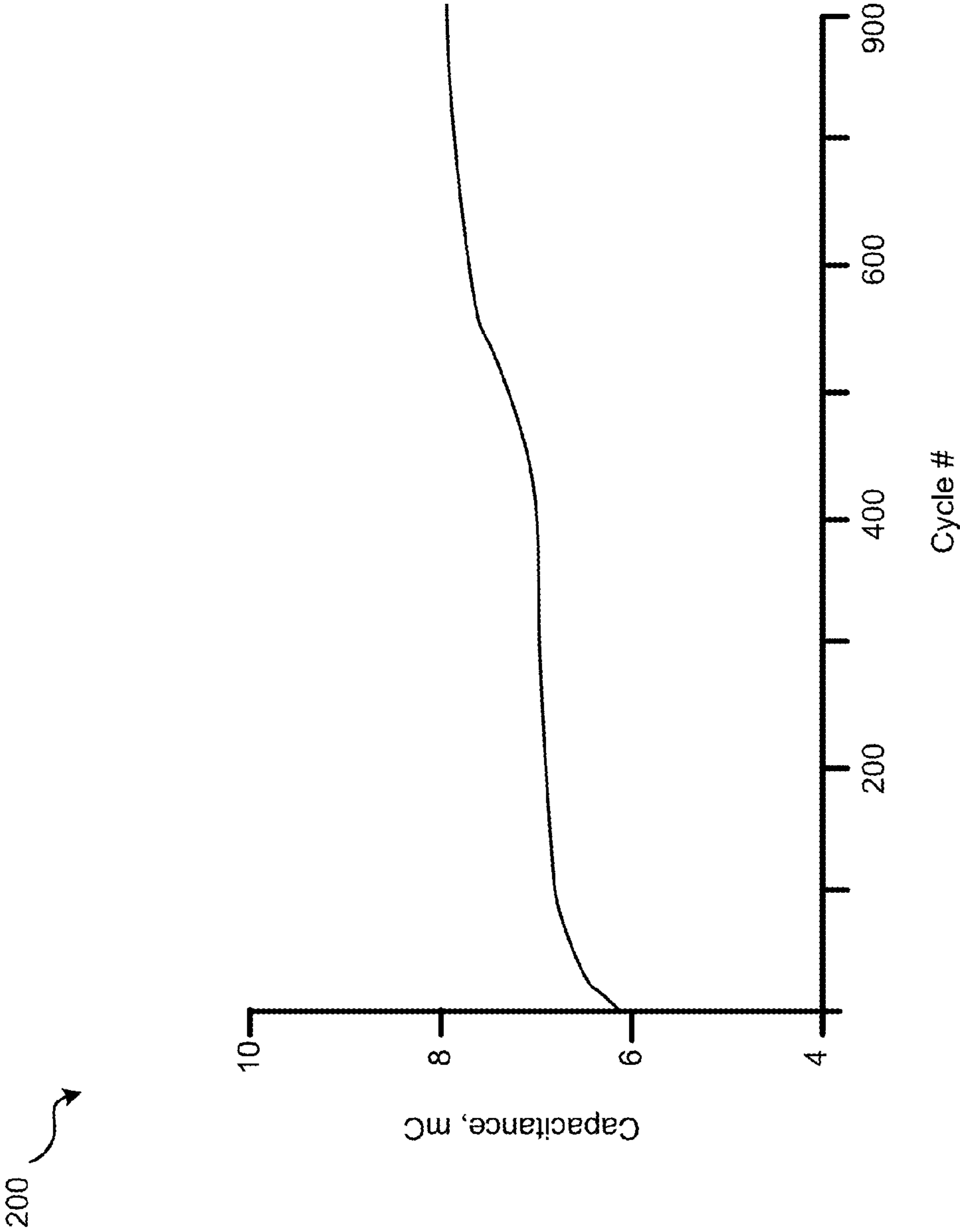


FIG. 2

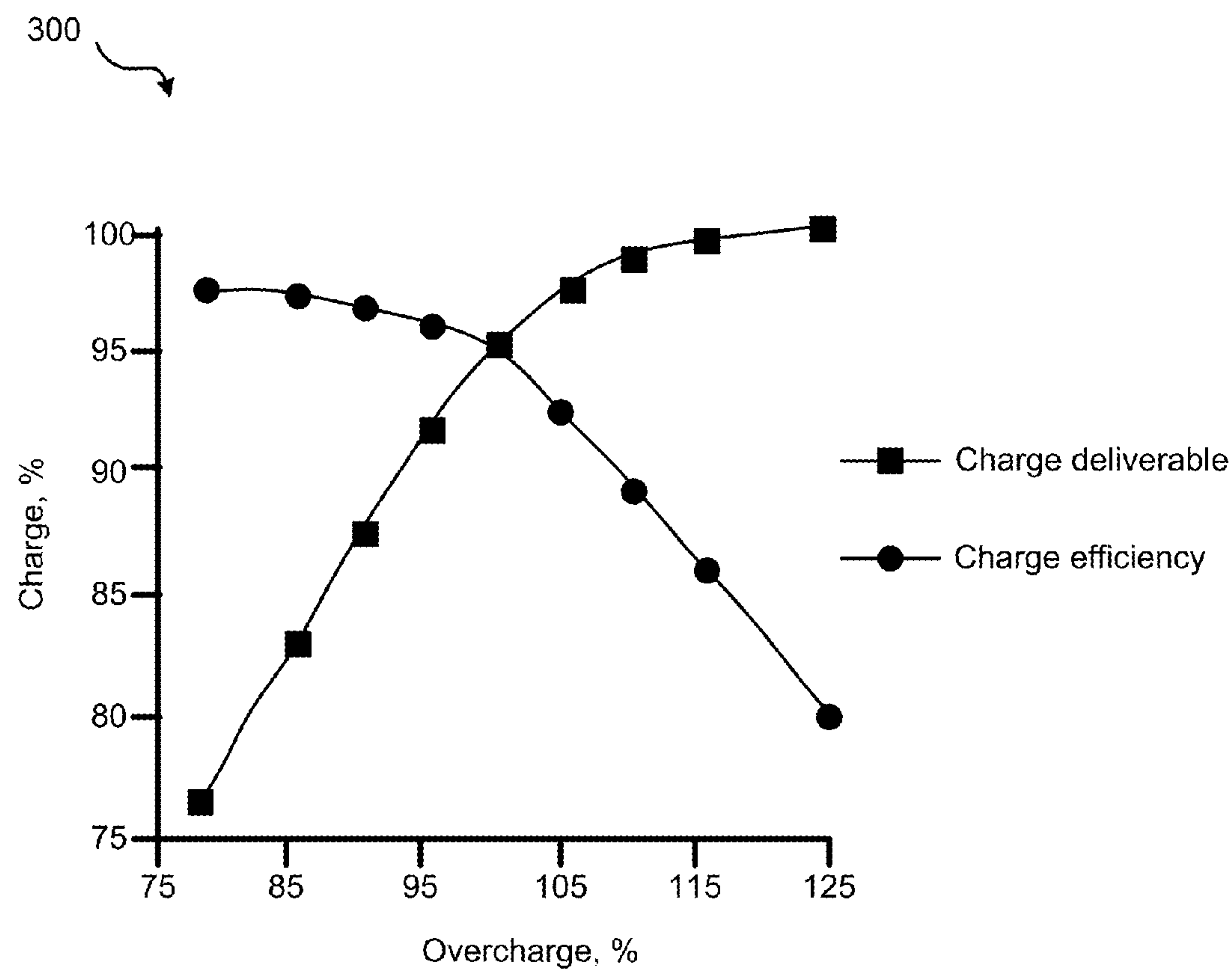


FIG. 3

400

Form the nickel oxide/hydroxide active film onto a substrate from a solution containing a nickelous salt and an electrolyte, where the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles, and where the nickel oxide/hydroxide active film has a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

402

FIG. 4

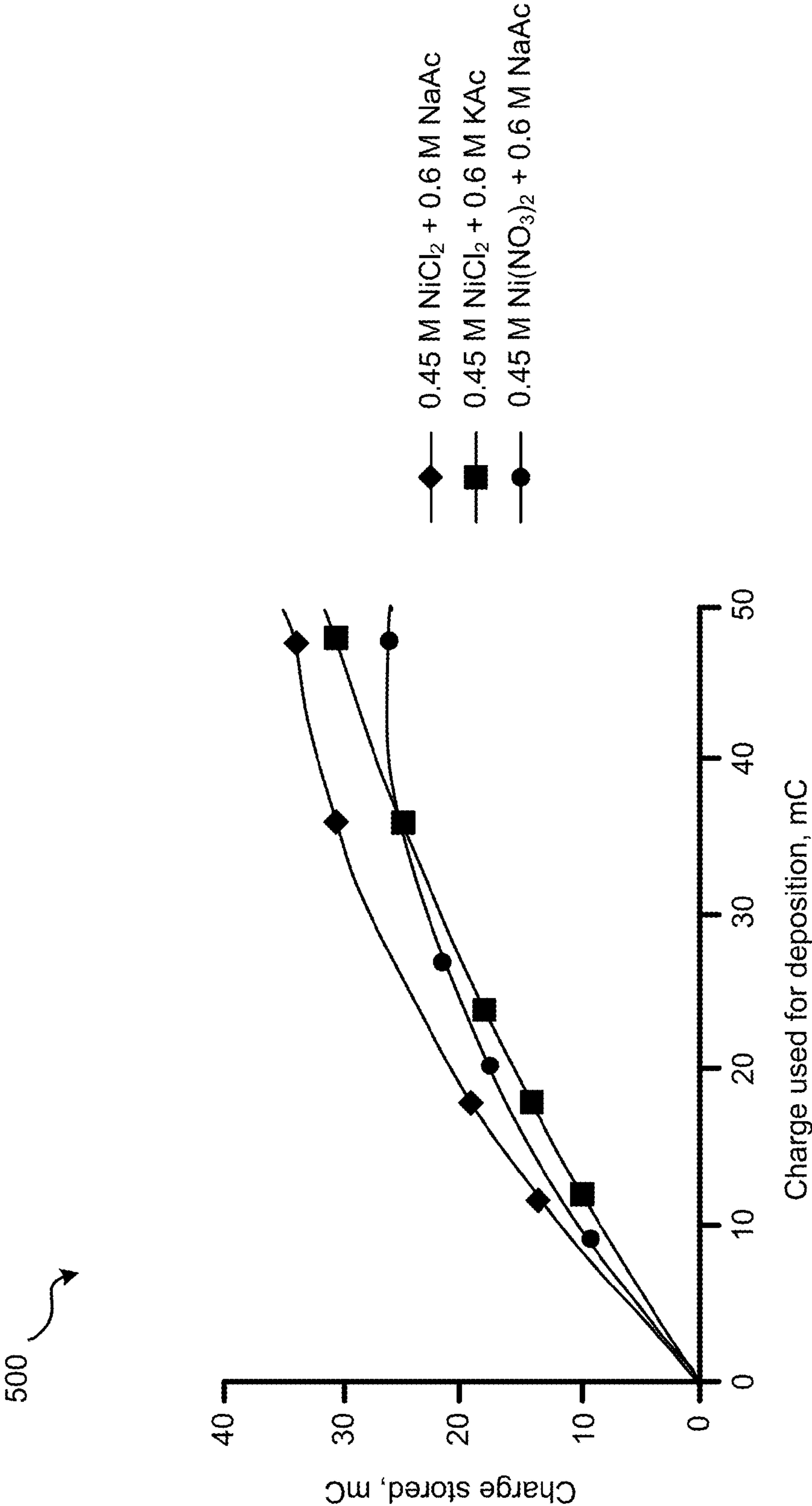


FIG. 5

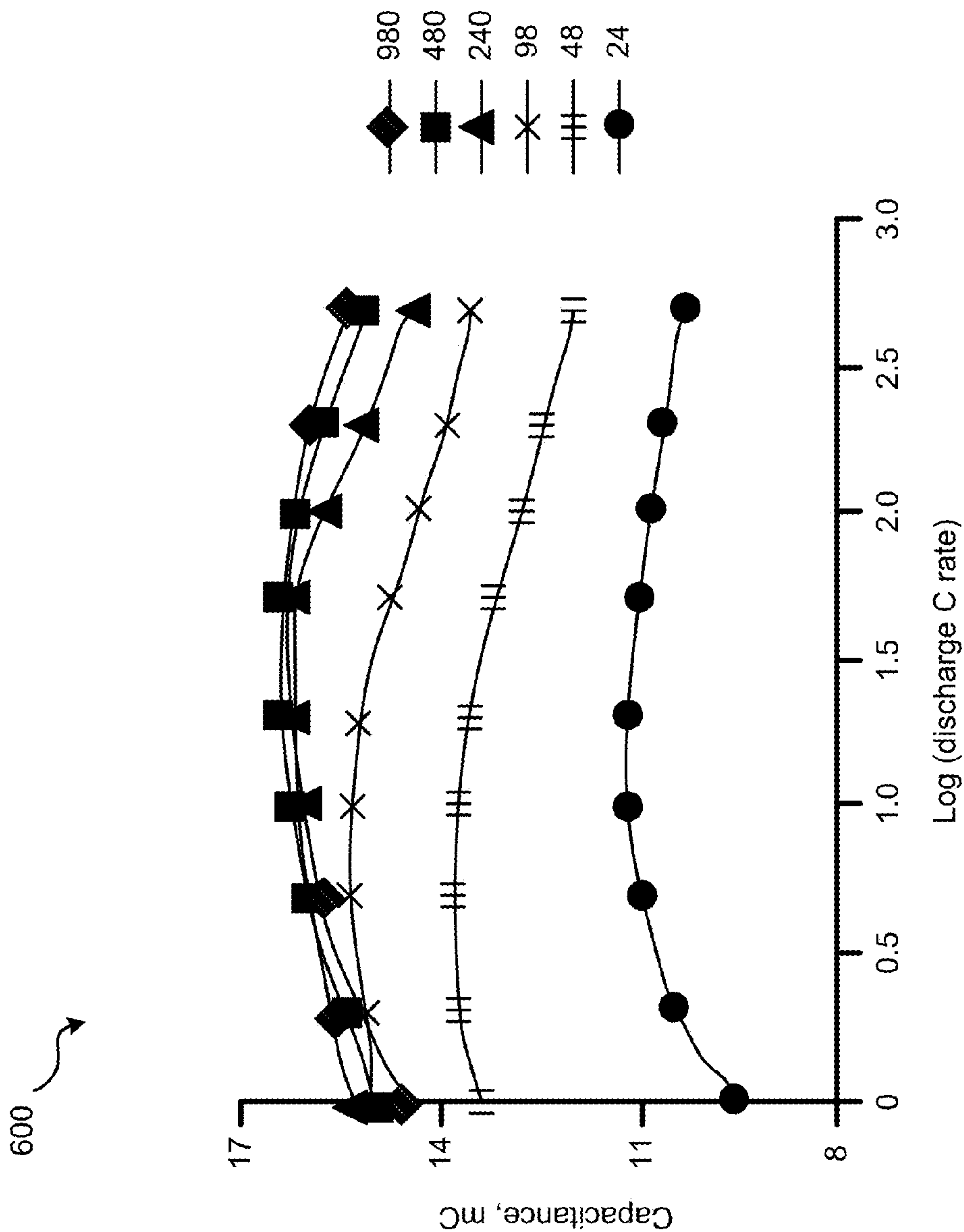


FIG. 6

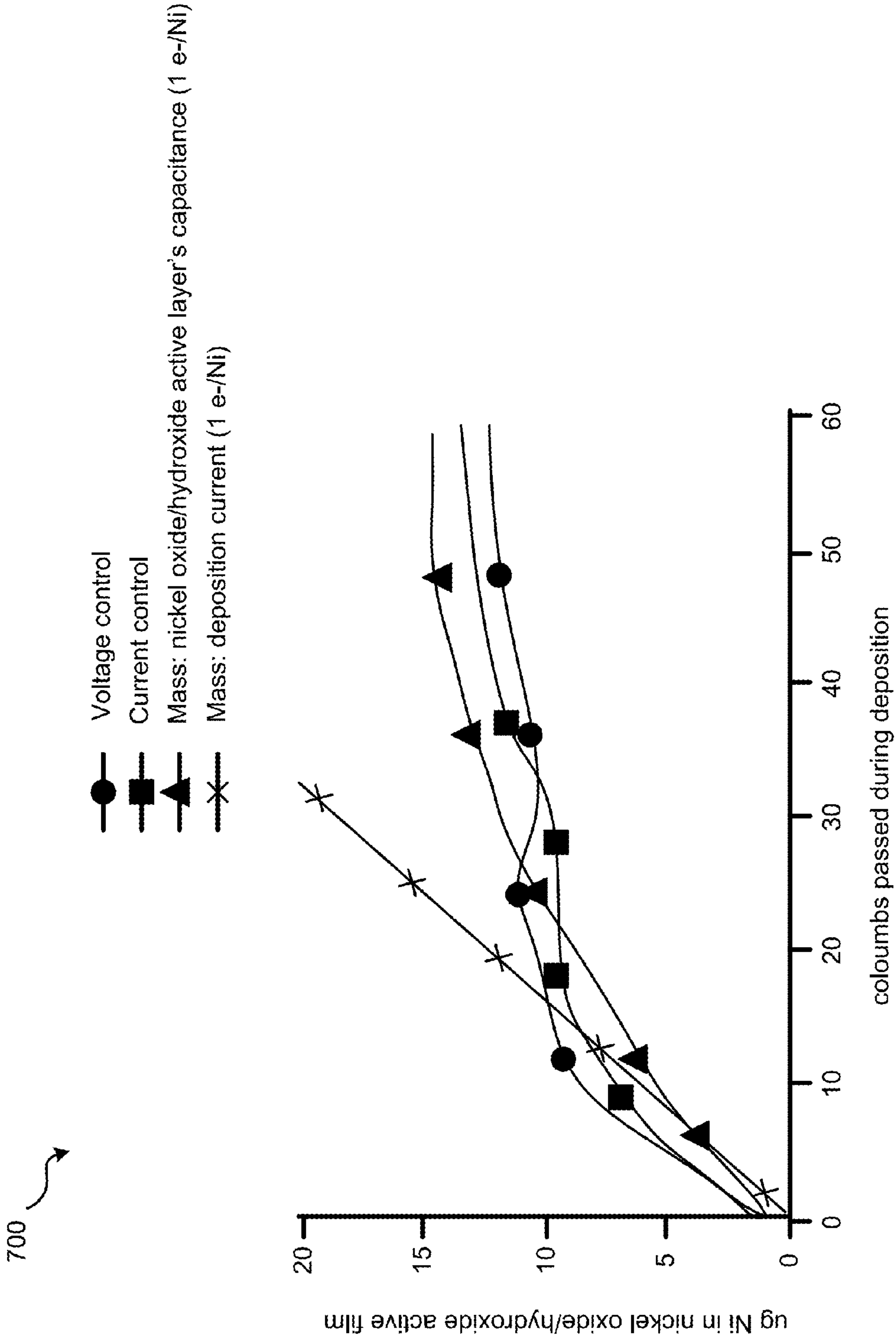


FIG. 7

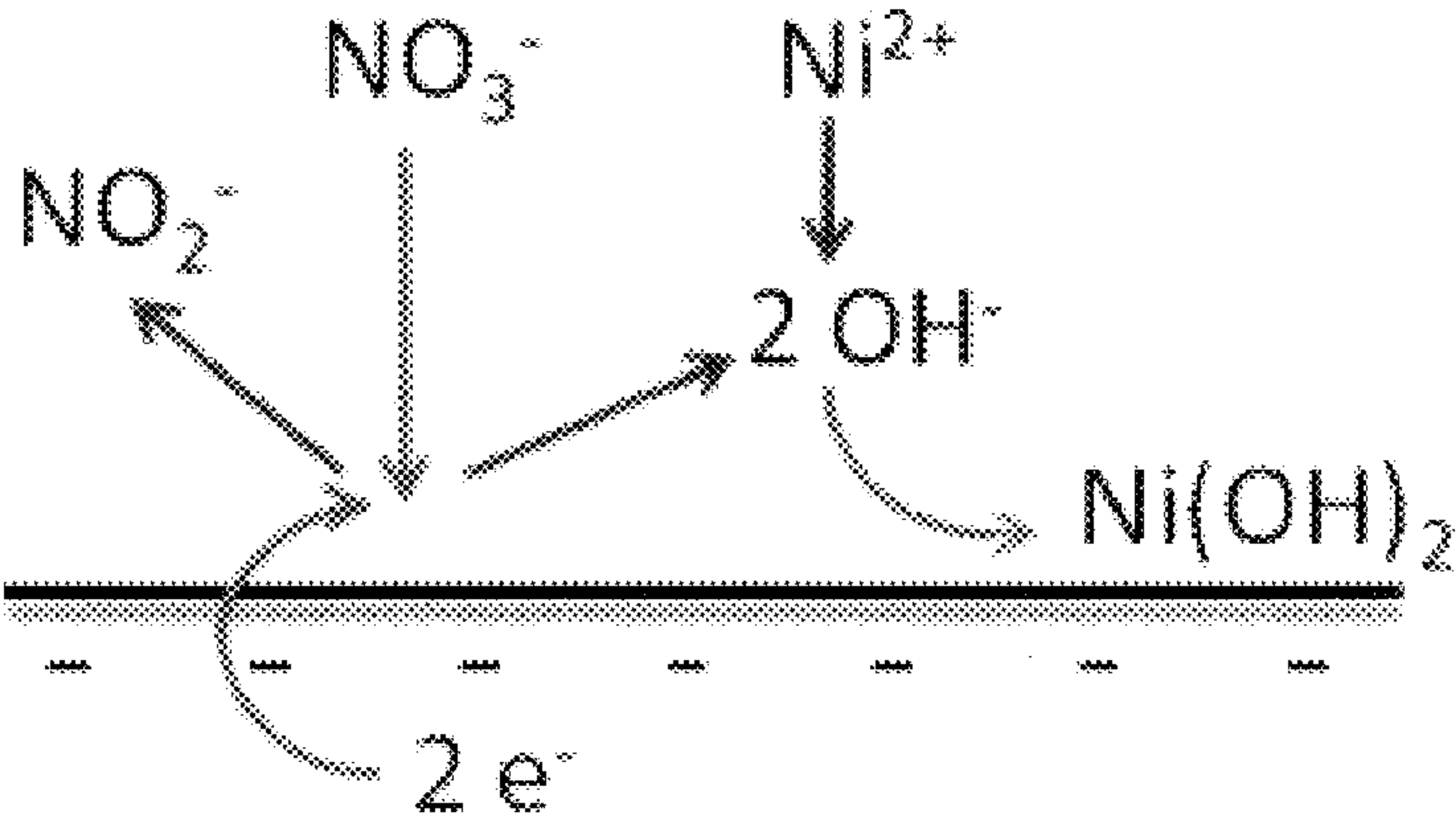


FIG. 8A

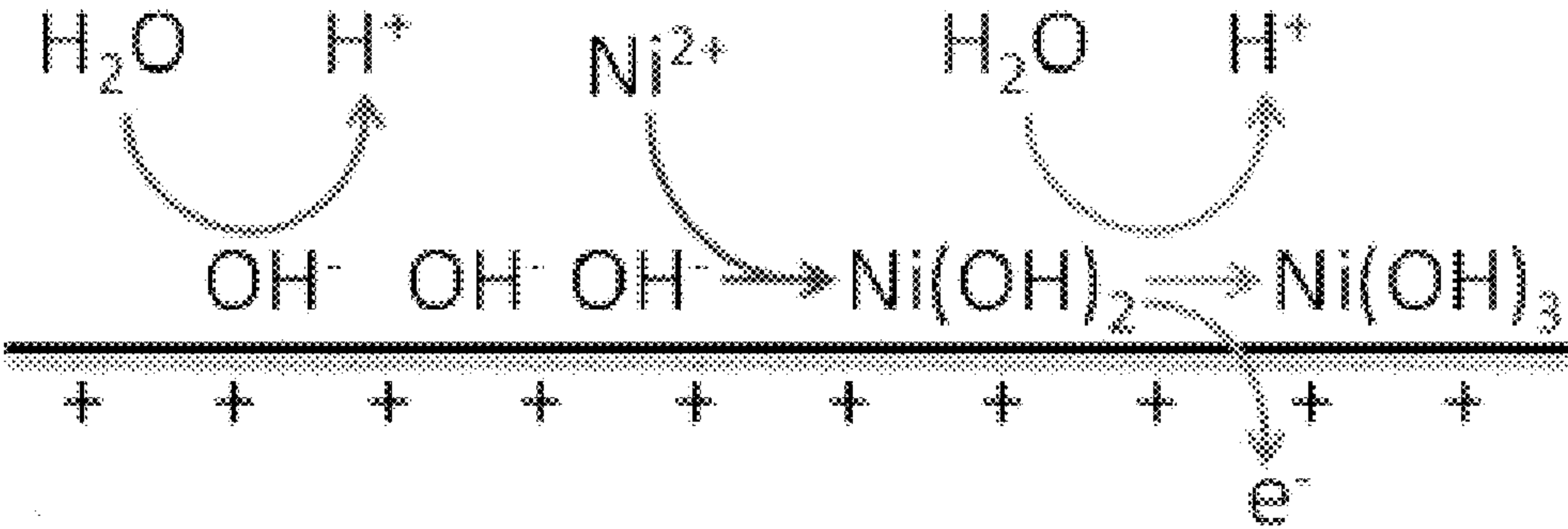


FIG. 8B

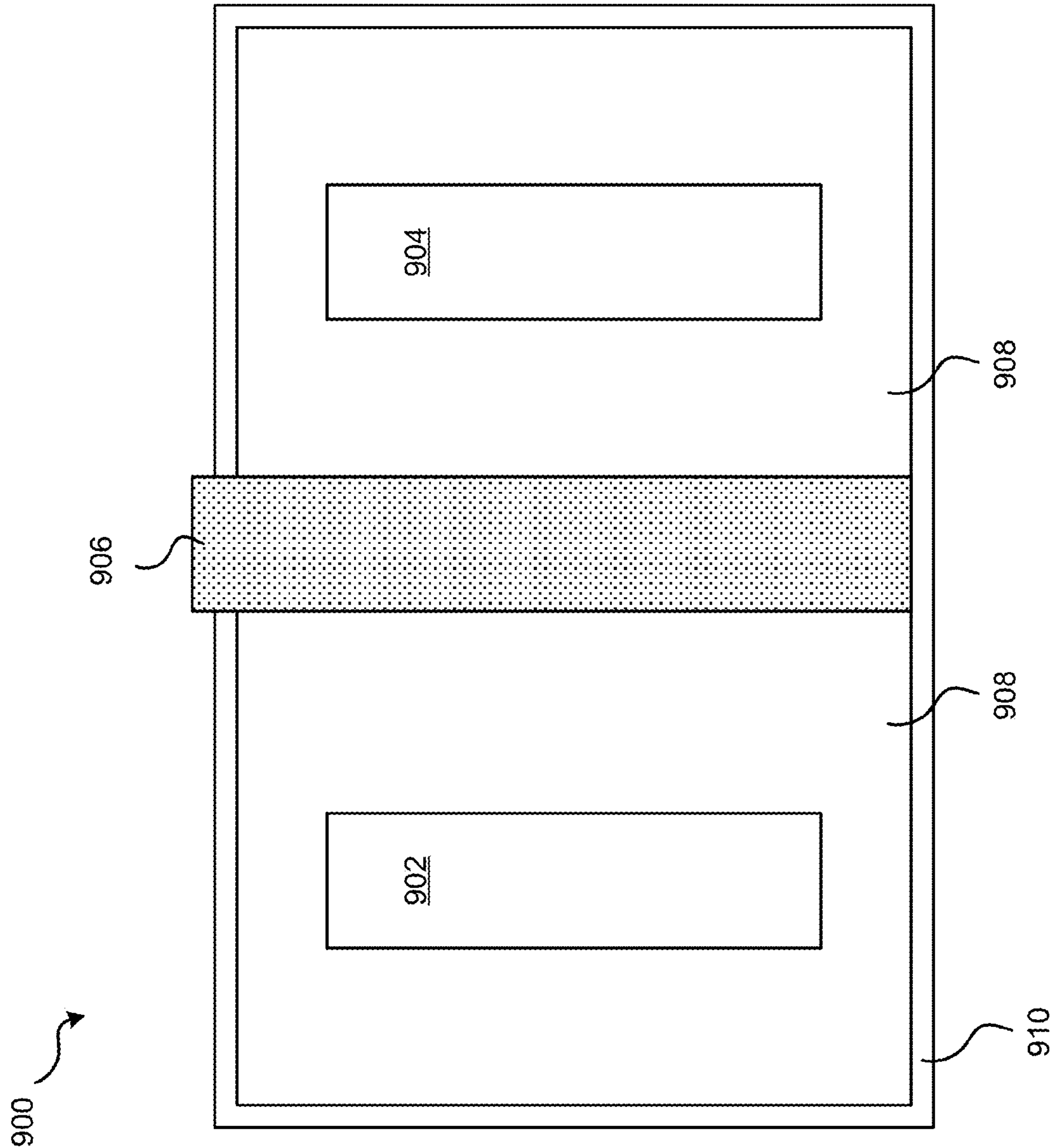


FIG. 9

HIGH ENERGY/POWER DENSITY NICKEL OXIDE/HYDROXIDE MATERIALS AND NICKEL COBALT OXIDE/HYDROXIDE MATERIALS AND PRODUCTION THEREOF

RELATED APPLICATIONS

[0001] This application claims priority to U.S. Provisional Application No. 61/565,444, filed Nov. 30, 2011, the contents of which are herein incorporated by reference.

[0002] The United States Government has rights in this invention pursuant to Contract No. DE-AC52-07NA27344 between the United States Department of Energy and Lawrence Livermore National Security, LLC for the operation of Lawrence Livermore National Laboratory.

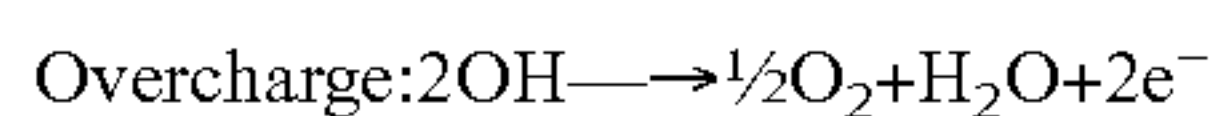
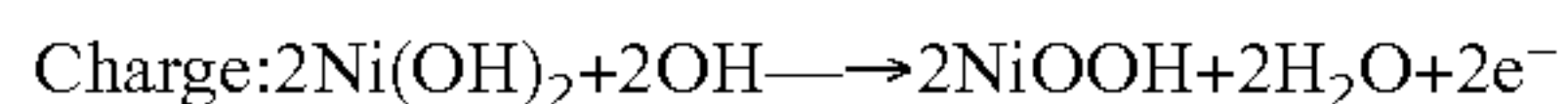
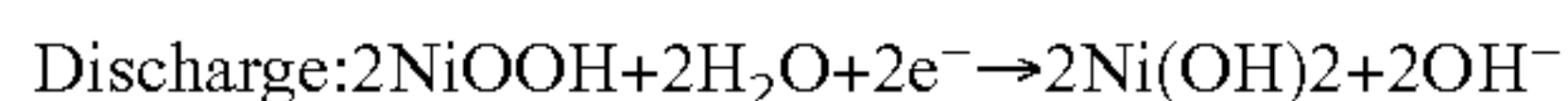
FIELD OF THE INVENTION

[0003] The present invention relates to high energy/power density materials, and more particularly to nickel oxide/hydroxide and nickel-cobalt oxide/hydroxide materials and related methods and/or uses.

BACKGROUND

[0004] Rapid technological developments in the electronics and computer industry have created a large consumer market for a variety of batteries. For example, batteries are used to power almost every portable electronic device, such as cell phones, laptop computers, camcorders, portable radios, cameras, etc. Consequently, the demand for compact, high-energy density batteries has been steadily increasing.

[0005] Nickel (III) oxide/hydroxide (NiOOH) is often used as the positive electrode, e.g. the cathode, in batteries and capacitors. When a battery is discharged, nickel (III) oxide-hydroxide is reduced to nickel (II) hydroxide. When the battery is overcharged, oxygen is produced at the nickel electrode and may recombine with any hydrogen present to form water. The simplified, representative electrochemical reactions at a nickel oxide/hydroxide electrode are as follows:



[0006] However, conventional nickel oxide-hydroxide electrodes generally exhibit a serious deficiency with regard to charge retention.

SUMMARY

[0007] According to one embodiment, a material includes a nickel oxide/hydroxide active film, wherein the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles, and wherein the nickel oxide/hydroxide active film has a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

[0008] Other aspects and embodiments of the present invention will become apparent from the following detailed description, which, when taken in conjunction with the drawings, illustrate by way of example the principles of the invention.

BRIEF DESCRIPTION OF THE DRAWINGS

[0009] For a fuller understanding of the nature and advantages of the present invention, reference should be made to the following detailed description read in conjunction with the accompanying drawings.

[0010] FIG. 1 shows plots of the charge/discharge curves for a nickel-cobalt oxide/hydroxide active film.

[0011] FIG. 2 shows plots of the capacitance with cycling for a nickel-cobalt oxide/hydroxide active film at 100% depth of discharge and 10% overcharge.

[0012] FIG. 3 shows plots of the charge efficiency (charge output/charge input) and charge deliverable (charge output delivered/maximum charge output deliverable with respect to the overcharge (charge input/maximum charge output) for a nickel-cobalt oxide/hydroxide active film.

[0013] FIG. 4 shows a flowchart of a method for forming a high energy/power density material including at least a nickel oxide/hydroxide active film according to one embodiment.

[0014] FIG. 5 shows plots of the charge stored in a nickel oxide/hydroxide active film formed from three solutions having various nickelous salts and electrolytes.

[0015] FIG. 6 shows plots of the dependence between charge storage performance and charge/discharge rates for a nickel oxide/hydroxide active film.

[0016] FIG. 7 shows plots of quantities of nickel deposited in a nickel oxide/hydroxide active film formed from a solution including 0.45 M Ni(NO₃)₂ and 0.3 M Ni(AC)₂.

[0017] FIGS. 8A and 8B show schematics of cathodic and anodic electrodeposition of nickel oxide/hydroxide, respectively.

[0018] FIG. 9 shows a schematic of a battery according to one embodiment.

DETAILED DESCRIPTION

[0019] The following description is made for the purpose of illustrating the general principles of the present invention and is not meant to limit the inventive concepts claimed herein. Further, particular features described herein can be used in combination with other described features in each of the various possible combinations and permutations.

[0020] Unless otherwise specifically defined herein, all terms are to be given their broadest possible interpretation including meanings implied from the specification as well as meanings understood by those skilled in the art and/or as defined in dictionaries, treatises, etc.

[0021] It must also be noted that, as used in the specification and the appended claims, the singular forms "a," "an" and "the" include plural referents unless otherwise specified.

[0022] The following description discloses several preferred embodiments of high energy/power density nickel oxide/hydroxide and nickel-cobalt oxide/hydroxide materials and/or related systems and methods.

[0023] According to one general embodiment, a material includes a nickel oxide/hydroxide active film, wherein the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles, and wherein the nickel oxide/hydroxide active film has a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

[0024] Conventional nickel electrodes generally consist of a nickel oxide-hydroxide slurry or paste pressed into a sintered or nonsintered nickel foam current collector. However

these conventional electrodes are often not compatible with modern current collectors, e.g. carbon-based and other types of current collectors, especially those possessing smaller and smaller pore sizes, as the active nickel material's particles are too large to be mechanically introduced into said pores. Furthermore, conventional nickel electrodes generally exhibit poor charge retention and energy densities.

[0025] Embodiments of the present invention overcome the aforementioned drawbacks by providing high energy/power density materials with physical characteristics including surprisingly high and improved charge retentions, charge/discharge rates, charge efficiencies, thermal management and cycle lives. The high energy/power density materials may constitute the charge storage material (e.g. the active material) for use in Ni cathodes of various battery formats, including, but not limited to, nickel-zinc, nickel-cadmium, nickel-metal hydride, nickel- H_2 , rechargeable batteries, etc. as well as various supercapacitors and pseudocapacitors.

[0026] According to one embodiment, a material, e.g. a high energy/power density material, includes a nickel oxide/hydroxide active film. The nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles. Stated another way, the nickel oxide/hydroxide film has a physical characteristic of being rechargeable to greater than 80% of an initial charge storage capacity over greater than 500 charge/discharge cycles. As used herein, a charge/discharge cycle refers to a cycle wherein the battery is fully discharged, i.e. attains an about 100% depth of discharge, and is subsequently charged to attain an about 100% state of charge.

[0027] In one approach, the nickel oxide/hydroxide film may have a charge/discharge rate of greater than about 100 C. The rate of attaining a 100% state of charge (or discharge) over a one hour time span corresponds to a rate of 1 C. Accordingly, a nickel oxide/hydroxide film having a charge/discharge rate of about 100 C may be able to attain a 100% state of charge/discharge in about 36 seconds. In another approach, the nickel oxide/hydroxide film may have a charge/discharge rate of greater than about 1000 C. Therefore, a nickel oxide/hydroxide film having a charge/discharge rate of about 1000 C may be able to attain a 100% state of charge/discharge in about 3.6 seconds. In other approaches, the charge/discharge rate may be in a range between 100 C and 1000 C.

[0028] In various embodiments, the nickel oxide/hydroxide active film may also have a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom. Additionally, it has been surprisingly found that, in various approaches, the nickel oxide/hydroxide active film may have a physical characteristic of storing electrons at equal to or greater than 1.25 electrons per nickel atom.

[0029] In yet another approach, the nickel oxide/hydroxide active film may have a thickness of about 20 to about 200 nm. According to an additional approach, the nickel oxide/hydroxide film may have a thickness of about 40 nm to about 100 nm.

[0030] In a further approach, the nickel oxide/hydroxide active film may have a physical characteristic of formation from electrodeposition, preferably anodic electrodeposition. For example, the nickel oxide/hydroxide active film may have a deposition thickness that is substantially uniform, such that a deposition thickness, e.g. in a thickness range of about 50 nm to 100 nm, may vary less than about ± 1 nm along sub-

stantially all codeposited portions thereof, e.g., along at least 85%, preferably at least 90%, of the codeposited portions.

[0031] In additional approaches, the high energy/power density material may include a porous substrate upon which the nickel oxide/hydroxide active film is deposited, preferably directly, thereupon. In some approaches the porous substrate may have pore sizes of about 0.1 to 1 μm . The pores sizes and distances between the pores in the porous substrate may also be uniform in more approaches. In alternate embodiments, the substrate may have other configurations, such as posts, ridges and channels, etc. Void spaces in such alternate embodiments may have similar dimensions as those set forth herein.

[0032] Moreover, in more approaches the substrate may include a porous carbon based structure. For example, in one approach, the substrate may include highly oriented paralytic graphite. In yet another approach, the substrate may include nickel such as metallic nickel, alloys of nickel (e.g. nickel aluminum), etc.

[0033] According to one embodiment, the nickel oxide/hydroxide film may include cobalt, resulting in a nickel-cobalt oxide/hydroxide active film. In one approach, the nickel-cobalt oxide/hydroxide active film may comprise a cobalt (Co) to nickel (Ni) ratio in a range of about 2:1 to about 1:2. In some approaches, the average oxidation state of Co and Ni in the nickel-cobalt oxide/hydroxide active film may be 2^+ , 3^+ or a combination thereof.

[0034] In another approach, the nickel-cobalt oxide/hydroxide active film may have a thickness of about 20 to about 200 nm, about 40 nm to about 100 nm, etc.

[0035] In yet another approach, the nickel-cobalt oxide/hydroxide active film may have a physical characteristic of formation from electrodeposition, preferably anodic electrodeposition. For example, in some approaches, the nickel-cobalt oxide/hydroxide active film may have a deposition thickness that is substantially uniform, meaning that the deposition thickness may vary less than about ± 1 nm along substantially all codeposited portions thereof.

[0036] In some approaches, the nickel-cobalt oxide/hydroxide active film may have a physical characteristic of storing electrons at equal to or greater than 1.25 electrons per nickel atom.

[0037] According to another approach, the nickel-cobalt oxide/hydroxide film may have a charge/discharge rate of greater than about 10 C. According to yet another approach, the nickel-cobalt oxide/hydroxide film may have a charge/discharge rate of greater than about 100 C. According to a further approach, the charge/discharge rate of the nickel-cobalt oxide/hydroxide may be in the range of 100 C and 1000 C.

[0038] In additional approaches, the nickel-cobalt oxide/hydroxide active film may be capable of a 100% depth of discharge at any discharge rate. Nonetheless, the material is able to be re-charged after reaching the 100% depth of discharge. The capability of the nickel-cobalt oxide/hydroxide active film to undergo 100% depth of discharge was surprisingly discovered by the inventors and was neither expected nor predictable based on the current literature.

[0039] In yet further approaches, it has been surprising and unexpectedly found that the nickel-cobalt oxide/hydroxide active film may be substantially stable. As used herein, stability is defined as the ability to discharge the same amount of charge through repeated charge/discharge cycles. For example, FIG. 1 depicts a plot 100 of the charge/discharge

curves for the nickel-cobalt oxide/hydroxide active film according to another embodiment. As shown in FIG. 1, the curve/discharge curves for nickel-cobalt oxide/hydroxide are substantially symmetric, which is indicative of the stability of an exemplary nickel-cobalt oxide/hydroxide active film.

[0040] With reference now to FIG. 2, a plot **200** depicting a capacitance (e.g. the ability to store an electrical charge) of a nickel-cobalt oxide/hydroxide active film that remains constant or increases over greater than about 500 cycles at charge/discharge rates of 10 C, an about 100% depth of discharge (at least 95% discharge), and an about 10% overcharge according to one illustrative embodiment. As used herein, overcharge corresponds to the percentage of the nominal (or actual) charge capacity of the film being defined as 100% state-of-charge. Charge input above the 100% state-of-charge level is defined as overcharge.

[0041] According to an exemplary approach, the nickel-cobalt oxide/hydroxide may have a physical characteristic of maintaining greater than about 90% charge over greater than about 800 cycles.

[0042] In other illustrative approaches, the nickel-cobalt oxide/hydroxide active film may have a physical characteristic of achieving about 97% charge efficiency (e.g. charge out/charge in) at 10 C. For instance, FIG. 3 shows a plot **300** of the charge efficiency and charge deliverable (charge output delivered/maximum charge output deliverable) for the nickel-cobalt oxide/hydroxide active film according to one embodiment.

[0043] Referring now to FIG. 4, a method **400** for forming a high energy/power density material including at least a nickel oxide/hydroxide active film, is shown according to yet another embodiment. As an option, the present method **400** may be implemented in conjunction with features from any other embodiment listed herein, such as those described with reference to the other FIGS. Of course, however, such method **400** and others presented herein may be used in various applications and/or in permutations, which may or may not be specifically described in the illustrative embodiments listed herein. Moreover, more or less operations than those shown in FIG. 4 may be included in method **400**, according to various embodiments.

[0044] As shown in FIG. 4, the method **400** includes forming the nickel oxide/hydroxide active film onto a substrate from a solution including a nickelous salt and an electrolyte. See step **402**. The nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles. In addition, the nickel oxide/hydroxide active film also has a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

[0045] According to one approach, the nickelous salt may be selected from the group consisting of: nickel acetate (NiAc), $\text{Ni}(\text{NO}_3)_2$, NiSO_4 , and NiCl_2 . The nickelous salts may have a concentration in the solution of greater than zero to about 1.2 M in some approaches.

[0046] According to another approach, the electrolyte may be at least one of NaNO_3 , lithium acetate (LiAc), potassium acetate (KAc), sodium acetate (NaAc), potassium fluoride (KF), sodium fluoride (NaF), Na_2SO_4 , and LiOH. In some approaches, the electrolyte may have a concentration in solution of about 0.1 M to about 1.2 M.

[0047] Referring now to FIG. 5, a plot **500** of the charge stored in a nickel oxide/hydroxide active film formed from three different solutions including a nickelous salts and an

electrolyte is shown according to various illustrative embodiments. In a preferred embodiment, the solution including a nickelous salt and an electrolyte may include 0.45 M NiCl_2 and 0.6 M NaAc. As shown in FIG. 5, such a solution including 0.45 M NiCl_2 and 0.6 M NaAc may yield the most active nickel oxide/hydroxide active film. As used herein, the activity of the nickel oxide/hydroxide film refers to charge storage performance (e.g. the film's ability to store charge, the film's capacitance, etc.).

[0048] In numerous embodiments, the activity of a nickel oxide/hydroxide film may be affected by the film's charge/discharge rates. For example, FIG. 6 illustrates the dependence between charge storage performance and charge/discharge rates for a nickel oxide/hydroxide active film formed from a solution including 0.45 M NiCl_2 and 0.6 M NaAc, according to one approach. As shown in FIG. 6, a preferred charge and discharge rate of the nickel oxide/hydroxide active film with respect to charge storage performance may be about 480 C and about 120 C, respectively. A rate of 980 C also showed excellent performance, inferring a preferred charge/discharge rate for this and other embodiments in a range of between about 120 C and about 880 C.

[0049] Additionally, in some approaches, a nickel oxide/hydroxide active film formed from a solution including about 0.45 M NiCl_2 and about 0.6 M LiAc may also exhibit large charge storage. Furthermore, in other approaches, the inclusion of up to 2 M KF (potassium fluoride) in the solution may increase the charge stored by up to 50%.

[0050] In a preferred embodiment, the electrolyte may include an acetate ion (Ac). In some approaches, the acetate ion electrolyte may be used for raising and buffering an OH[−] concentration to a pH range of between about 7 to about 9, which may represent an upper solubility limit for large concentrations of Ni^{2+} ions (e.g. greater than 0.1 M).

[0051] Referring now to the chart **700** of FIG. 7, a quantity of nickel deposited in a nickel oxide/hydroxide active film formed from a solution including 0.45 M $\text{Ni}(\text{NO}_3)_2$ (a nickelous salt) and 0.3 M $\text{Ni}(\text{AC})_2$ (an electrolyte) is shown according to another illustrative embodiment. In some approaches, the quantity of nickel deposited in the nickel oxide/hydroxide active film may be determined by dissolving the nickel oxide/hydroxide active film in nitric acid and then determining the Ni content with inductively coupled plasma mass spectrometry (ICP-MS).

[0052] As shown in FIG. 7, the mass of the nickel deposited in the nickel oxide/hydroxide active film is approximately independent of whether current (galvanostatic) or voltage (potentiostatic) control methods are used to deposit the nickel oxide/hydroxide active film. In addition, the mass of the deposited nickel as expected based on a capacitance metric is plotted in FIG. 7 using the assumption that one electron is stored per nickel atom. Further, the mass of the deposited nickel as expected from a simplified deposition mechanism, e.g. $\text{Ni}^{2+}_{(aq)} + 3 \text{OH}^{-}_{(aq)} \rightarrow \text{Ni}(\text{OH})_{3(s)} + e^{-}$, is also plotted in FIG. 7 using the assumption that one nickel atom is deposited for every electron passed during the deposition process. Not wishing to be bound by any particular theory, it is presently believed that the majority of the nickel initially deposited may have formed in the Ni^{2+} state because there may be more Ni than could have been deposited according to the above described deposition mechanism.

[0053] Preferably, the quantity of nickel deposited in the oxide/hydroxide active film increases linearly with deposition duration so as to facilitate control over a thickness of the

nickel oxide/oxide active film. In some approaches, the thickness of the nickel oxide/hydroxide active film may be in a range of about 20 to about 200 nm.

[0054] Additionally, the method **400** for forming the high energy/power density material may further comprise depositing the nickel oxide/hydroxide active film on a substrate via electrodeposition. Electrodeposition processes may include cathodic deposition (as shown in FIG. **8A**), anodic deposition (as shown in FIG. **8B**), etc.

[0055] In preferred embodiments, the method for forming the high energy/power density material may comprise depositing the nickel oxide/hydroxide active film on a substrate via anodic electrodeposition. In various approaches, anodic deposition may include contacting a substrate with an aqueous solution including a nickelous salt (and therefore nickelous Ni^{2+} ions) and at least one electrolyte, followed by application of a current/voltage to the substrate in order to deposit the nickel as a nickel oxide/hydroxide active film coating the substrate. Preferably, the anodic deposition may result in a substantially even distribution of a nickel oxide/hydroxide active film over the substrate or other complex surfaces due, at least in part, to kinetically governed surface-dependent reactions. For example, the anodic deposition may produce a nickel oxide/hydroxide film with controllable and uniform thickness (e.g. the thickness may vary less than about ± 1 nm along all codeposited portions thereof) in some approaches.

[0056] In various approaches, the stability of a nickel oxide/hydroxide active film formed, e.g. via anodic electrodeposition, may be affected by the film's charge and discharge rates. As noted above, the stability of the nickel oxide/hydroxide film may be defined as the ability to discharge nearly the same amount of charge through repeated charge/discharge cycles. In some approaches, a benchmark for the stability of the nickel oxide/hydroxide active film may comprise maintaining, retaining, etc. greater than about 80% of its charge storage capacity when the nickel oxide/hydroxide active film is charged at preferred C rates, e.g. 480 C, and overcharged by about 30% (e.g. where the amount of charge applied to the nickel oxide/hydroxide active film is about 130% of the storable charge in the material).

[0057] In further approaches, the method for forming the high energy/power density material comprising a nickel oxide/hydroxide active film may further include modifying the pH of the solution including the nickelous salt and an electrolyte. In some instances, modifying the pH of this solution may affect the deposition efficiency of the nickel oxide/hydroxide active film on the substrate as well as the charge storage of the nickel oxide/hydroxide active film. Consequently, in some approaches, the nickel oxide/hydroxide active film may be charged/discharged in solutions with a pH range of about 1 to about 6 M KOH. In preferred approaches, the nickel oxide/hydroxide active film may be charged/discharged in about 3 M or about 6 M KOH.

[0058] Further, in yet another embodiment, the method for forming a high energy/power density material may include forming a nickel-cobalt oxide/hydroxide active film onto a substrate from a solution including a nickelous salt and a cobalt electrolyte.

[0059] In one approach, the nickel-cobalt oxide/hydroxide active film may be deposited on a substrate via electrodeposition, preferably anodic electrodeposition.

[0060] In conventional use, the inclusion of cobalt (Co) in battery materials is thought to persist in the inactive yet conductive 3^+ state. However, the inclusion of 1 Co^{2+} :100 Ni^{2+} in

the solution, e.g. the anodic electrodeposition solution, may result in nickel oxide/hydroxide active film having a cobalt to nickel ratio of about 2:1 in some approaches. In other approaches, the nickel-cobalt oxide hydroxide active film formed from a solution containing a nickelous salt and a cobalt electrolyte may have a cobalt to nickel ratio in a range from about 1:2 to about 2:1.

[0061] In another approach, the cobalt oxide/hydroxide may deposit faster than nickel at lower deposition potentials.

[0062] In yet another approach, the nickel-cobalt oxide/hydroxide active film may store greater than about 0.5 electron per metal atom.

[0063] In further approaches, the solution including a nickelous salt and a cobalt electrolyte may contain also contain a second electrolyte in addition to the cobalt electrolyte, such as LiAc, NaAc, KAc, NaNO_3 , NaF, KF and Na_2SO_4 .

[0064] Referring now to FIG. **9**, a battery **900** is shown according to one embodiment. As an option, the battery **900** may be implemented in conjunction with features from any other embodiment listed herein, such as those described with reference to the other FIGS. Of course, however, said battery **900** may be used in various applications and/or in permutations, which may or may not be specifically described in the illustrative embodiments listed herein.

[0065] As shown in FIG. **9**, a battery **900** may include a cathode **902**, an anode **904**, an electrolyte permeable separator **906** between the anode and the cathode, and an electrolyte solution **908** contacting both the anode **904** and the cathode **902**. In addition, the battery may include a housing **910**.

[0066] In some approaches, the anode **904** may include an anode active material comprising zinc or zinc alloy particles. In other approaches, the electrolyte solution **908** may include an aqueous solution of potassium hydroxide, sodium hydroxide, lithium hydroxide, etc.

[0067] In one embodiment, the battery **900** may include a cathode **902** comprising: a substrate having the nickel oxide/hydroxide active film deposited thereon, where the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles and also has a physical characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

[0068] While various embodiments have been described above, it should be understood that they have been presented by way of example only, and not limitation. For example, any one embodiment may be implemented in conjunction with features from any other embodiment listed herein, such as those described with reference to the other FIGS. Further, the embodiments may be used in various applications, devices, systems, methods, etc. and/or in various permutations, which may or may not be specifically described in the illustrative embodiments listed herein. Thus, the breadth and scope of the embodiments should not be limited by any of the above-described exemplary embodiments, but should be defined only in accordance with the following claims and their equivalents.

What is claimed is:

1. A material, comprising:

a nickel oxide/hydroxide active film, wherein the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 80% charge over greater than 500 charge/discharge cycles, and wherein the nickel oxide/hydroxide active film has a physical

characteristic of storing electrons at greater than about 0.5 electron per nickel atom.

2. The material of claim 1, wherein the nickel oxide/hydroxide active film has a thickness of about 20 to about 200 nm.

3. The material of claim 1, wherein the nickel oxide/hydroxide active film has a deposition thickness that varies less than about ± 1 nm along all codeposited portions thereof, wherein the thickness of the nickel oxide/hydroxide active film is in a range of about 50 to about 100 nm.

4. The material of claim 1, wherein the nickel oxide/hydroxide film has a charge rate of greater than about 100 C per hour.

5. The material of claim 1, wherein the nickel oxide/hydroxide film includes cobalt.

6. The material of claim 5, wherein the nickel oxide/hydroxide active film has a physical characteristic of maintaining greater than about 90% charge over greater than about 800 cycles.

7. The material of claim 5, wherein the nickel oxide/hydroxide active film comprises a cobalt (Co) to nickel (Ni) ratio of about 2:1 to about 1:2.

8. The material of claim 5, wherein the nickel oxide/hydroxide active film is capable of a 100% depth of discharge at varying discharge rates.

9. The material of claim 1, further comprising a substrate upon which the nickel oxide/hydroxide active film is deposited, wherein the substrate is porous.

10. The material of claim 1, further comprising a substrate upon which the nickel oxide/hydroxide active film is deposited, wherein the substrate includes highly oriented paralytic graphite.

11. The material of claim 1, further comprising a substrate upon which the nickel oxide/hydroxide active film is deposited, wherein the substrate includes nickel.

12. A method for forming the material of claim 1, the method comprising: forming the nickel oxide/hydroxide active film onto a substrate from a solution including a nickelous salt and an electrolyte.

13. The method of claim 12, wherein the nickelous salt is selected from a group consisting of: nickel acetate (NiAc), $\text{Ni}(\text{NO}_3)_2$, NiSO_4 , and NiCl_2 .

14. The method of claim 12, wherein the electrolyte is at least one of potassium acetate (KAc) and sodium acetate (NaAc).

15. The method of claim 12, wherein the electrolyte is at least one of potassium fluoride (KF) and sodium fluoride (NaF).

16. The method of claim 12, wherein the electrolyte is selected from a group consisting of: LiAc, NaAc, KAc, NaNO_3 , NaF, KF and Na_2SO_4 .

17. The method of claim 12, further comprising depositing the nickel oxide/hydroxide active film on a substrate via anodic electrodeposition.

18. The method of claim 12, wherein the solution has a pH less than about 6.

19. A battery, comprising:

a cathode, comprising: a substrate having the nickel oxide/hydroxide active film of claim 1 deposited thereon.

20. The battery of claim 19, further comprising an anode and an electrolyte solution.

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